TORSIONAL SUBSURFACE IMAGING USING ATOMIC PROBE MICROSCOPY

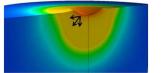
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INTRODUCTION

- Torsional subsurface probe microscopy (TSPM) is a non invasive technique that allows the detection of features below the surface of a sample, enhancing the contrast at the edges.
- > Excitation of a sample parallel to its surface, at the cantilever's *contact torsional resonant frequency*, f_0^{CT} , induces the torsional oscillation of the cantilever in contact with the sample.
- Example of application, torsional APM allows the detection of in-plane defects such as delamination, edge dislocations or stacking faults, essential to detect in the semicon industry where high epitaxial surface quality is essential in order to prevent adverse effects on device characteristics.

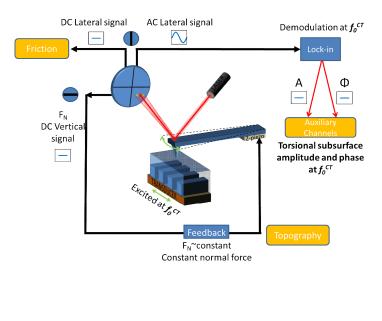
RESULTS

A stress field below the surface is induced due to the force applied by the tip.



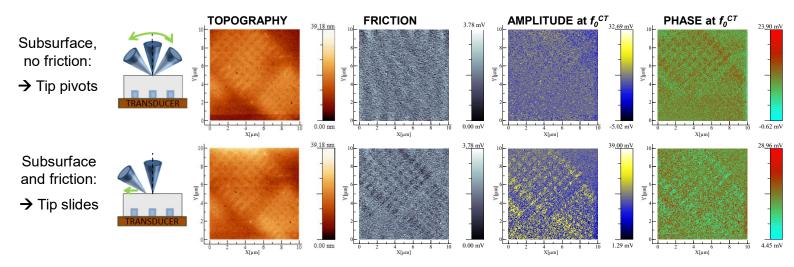
TECHNIQUE

> Amplitude and phase (demodulated at f_0^{CT}) contain information of subsurface features with enhancement of boundaries between different phases of the material or defects below the surface.

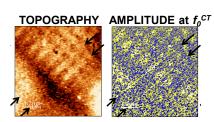




- > The Physical contributions to lateral signal come from:
 - 1) Subsurface shear elasticity \rightarrow Conservative
 - 2) Friction \rightarrow Dissipation of energy



Subsurface torsional amplitude shows buried features not visible in topography



SUMMARY

- TSPM is a promising non-invasive technique to obtain enhancement of boundaries or in planedefects buried below a surface.
- > Torsional signal gives information of dissipation at the surface (*friction*) and the shear elastic properties below the surface (*torsional subsurface*).